Batch production

Beneq P1500

OVERVIEW



The Beneq P1500 is the world's largest ALD reactor. With a vacuum chamber width of 1.7 meters, this tool is uniquely designed to coat very wide area substrates and large batches of 3D components. As the latest innovation in Beneq's P-Series, the P1500 continues to enable ALD on the biggest scale with viable high-volume manufacturing solutions.

FEATURES

Size

Accommodate parts up to 1300 × 2400 mm in size or coat batches of parts in the 300 to 1000 mm size range in a reaction chamber fitted perfectly for your use case.

Enablement

The P1500 enables the introduction of ALD to applications which were not feasible before, like depositing optical coatings on astronomical mirrors.

Robustness

Continuously switchable reaction chambers and a proprietary pre-heating oven allow users to enjoy maximum tool uptime and easy maintenance.

Substrate examples

- Generation 4 to 6 display glass
- Photovoltaic glass sheets
- Astronomical mirrors
- Semiconductor chamber lids, liners & showerheads
- Printed circuit boards

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SPECIFICATIONS

Process type	Thermal ALD
Integration	Stand-alone
Dimensions (L x W x H)	6195 × 2480 × 2600 mm
Vacuum chamber dimensions	W: 1700 mm
Temperature range	25-550 °C
Substrate type	• Glass or metal sheets • 3D and freeform parts
Substrate space	1300 x 2400 x 750 mm

BATCH PRODUCTION EQUIPMENT

Beneq’s P-series provides the largest-scale, general-purpose ALD production systems ideal for coating diverse substrate types and thick films. It is easy to scale up ALD deposition from the R&D phase to full manufacturing workflows.



Beneq P400A

Large scale, general purpose ALD production systems ideal for coating diverse substrate types and thick films.



Beneq P800

The Beneq P800 is specifically designed to coat big parts of complex shapes or large batches of smaller parts.